

Viacarbon

Carbon Nanotubes for Interconnects and Switches

John Robertson

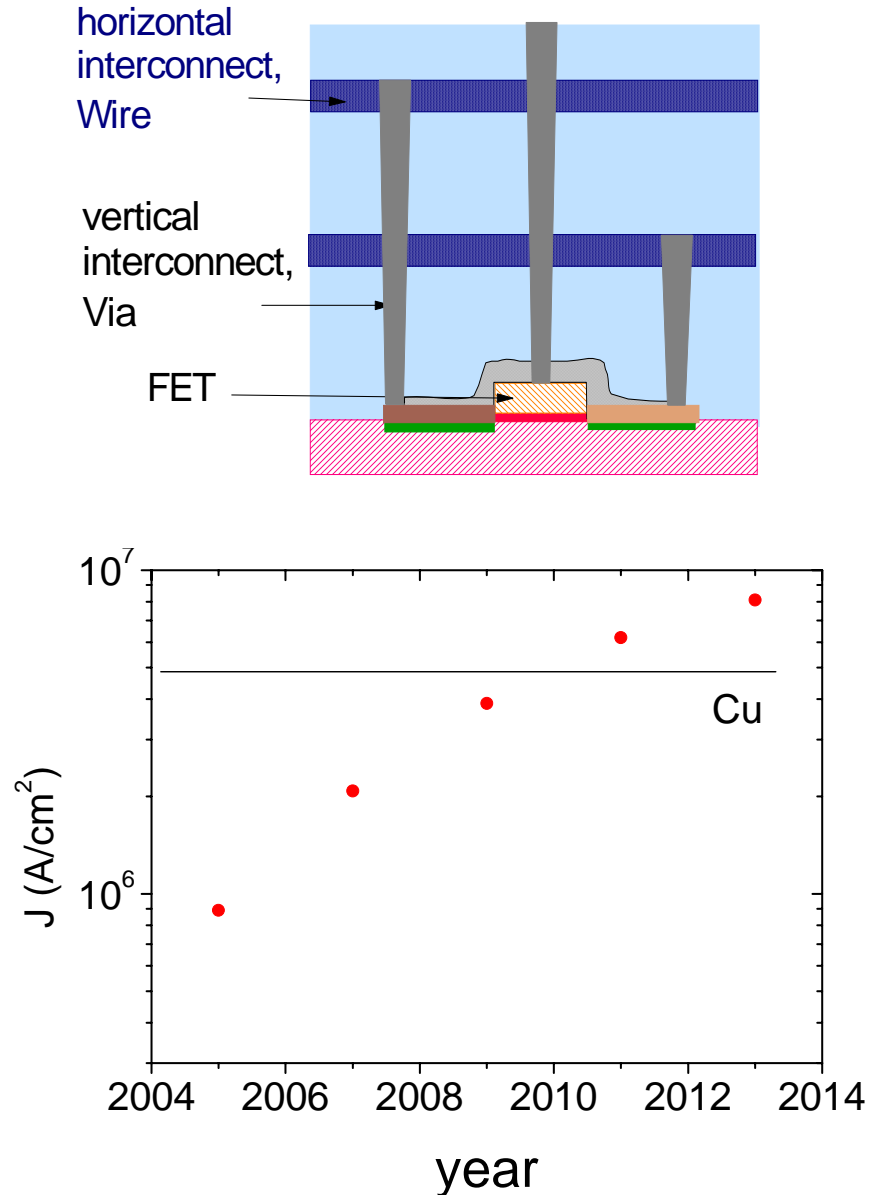
Cambridge University

Partners

- 1 Cambridge University, Dept. Engineering (Robertson)
- 2 CEA (Grenoble) Leti, Liten (M Scannell..)
- 3 Ecole Polytechnique Federale Lausanne (Adrian Ionescu)
- 4 Intel (Ireland) (Jenny Patterson)

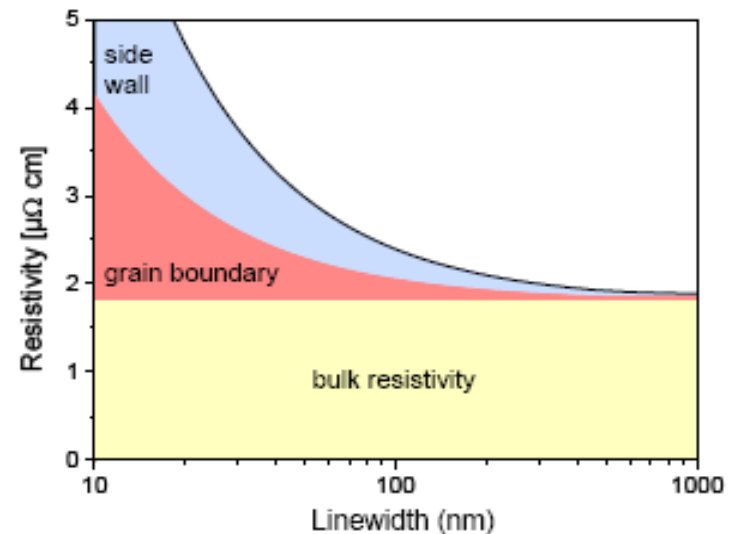
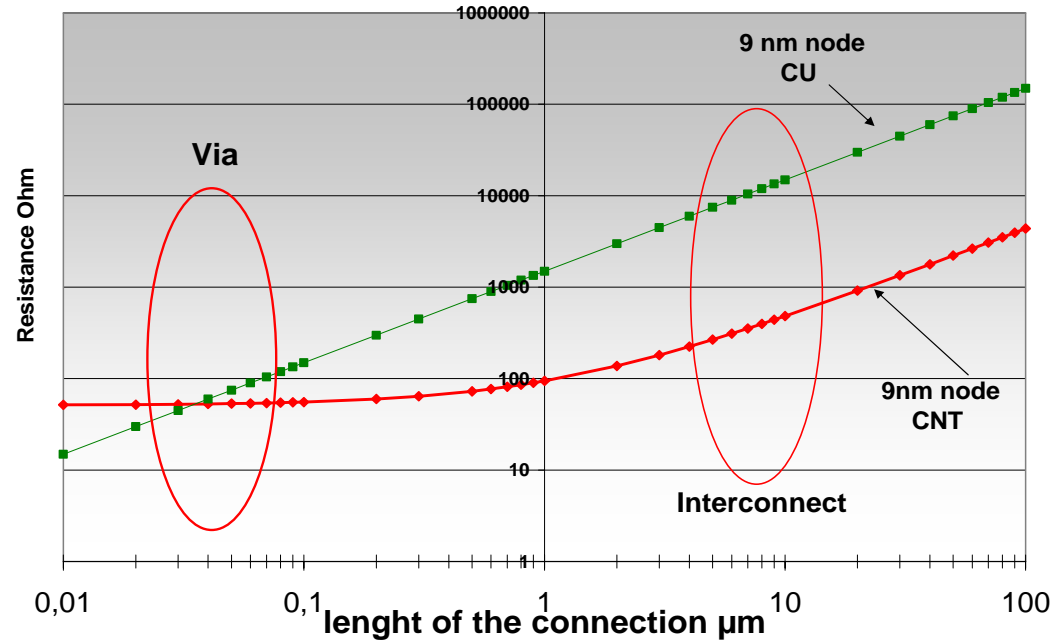
Background

- ITRS roadmap needs interconnects with $J > 5 \cdot 10^6 \text{ A/cm}^2$ beyond 22 nm node
- beyond limit of Cu
- Carbon nanotubes are only material to carry $J = 10^9 \text{ A/cm}^2$ without failure by electromigration
- ‘There is no (electrical) alternative’
- *But, practical implementation of CNT interconnects is quite uncertain, no technology*



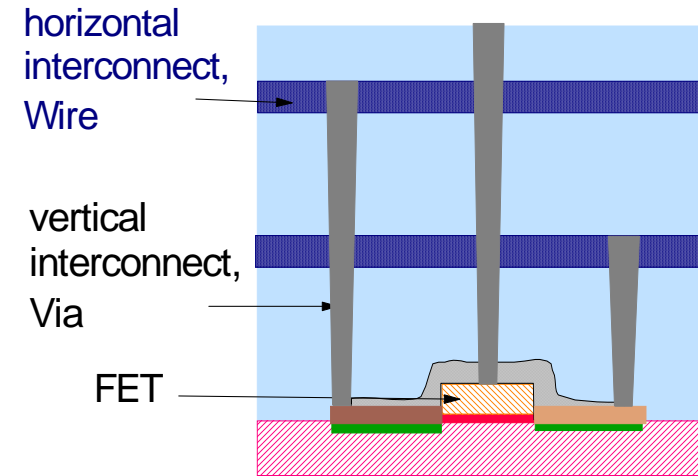
Requirement

- CNTs = 1D conductors, limited by quantum of conductance, $G_0 = 4h/e^2/\text{channel} \rightarrow R = 6.5\text{K}\Omega$
- G_0 acts as series resistance
- Difficult to get R below Cu for vertical Vias, but easier for horizontal Wires
- Need very high density of CNT channels in parallel
- Need single-walled nanotubes
- densities over 10^{13} cm^{-2}
- 3 nm spacing



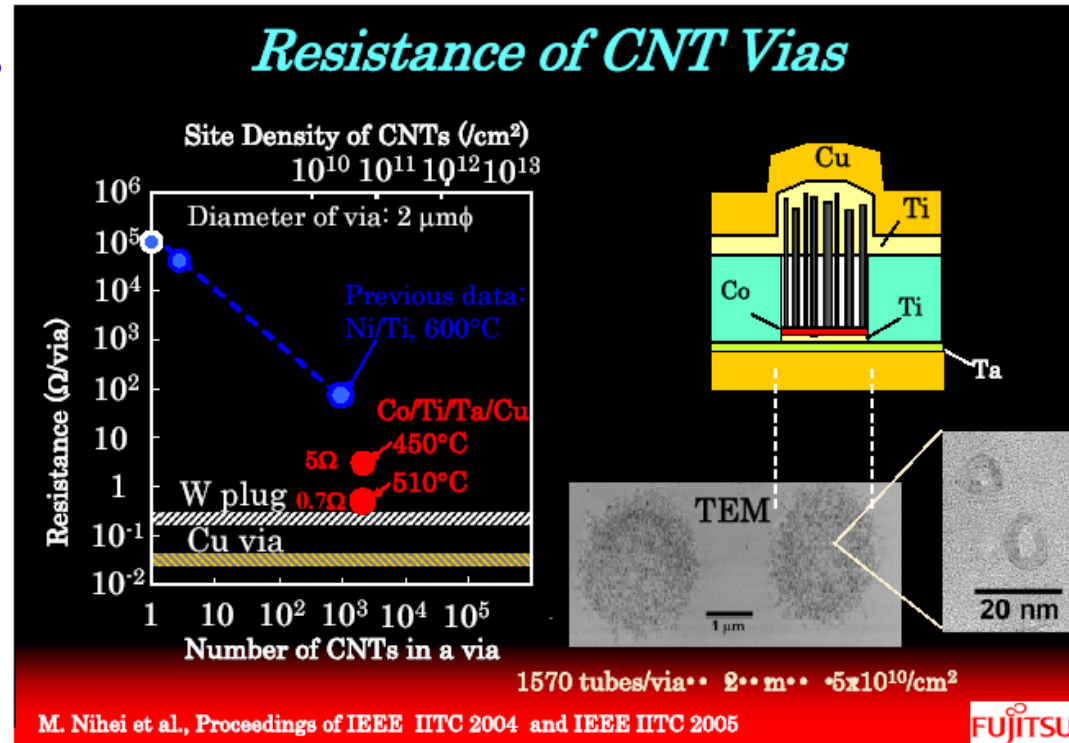
Objectives

- Develop an industry-compatible process for vertical interconnects
- Develop an industry-compatible process for horizontal interconnects
- Optimize growth catalyst and process conditions for SWNT density $\sim 10^{13} \text{ cm}^{-2}$
- Low resistivity contacts, total $R < 50 \Omega$
- Fabricate MNWT-based NEMS capacitive switch,
 - $C_{\text{on}}/C_{\text{off}} > 100$ for 2-5 GHz



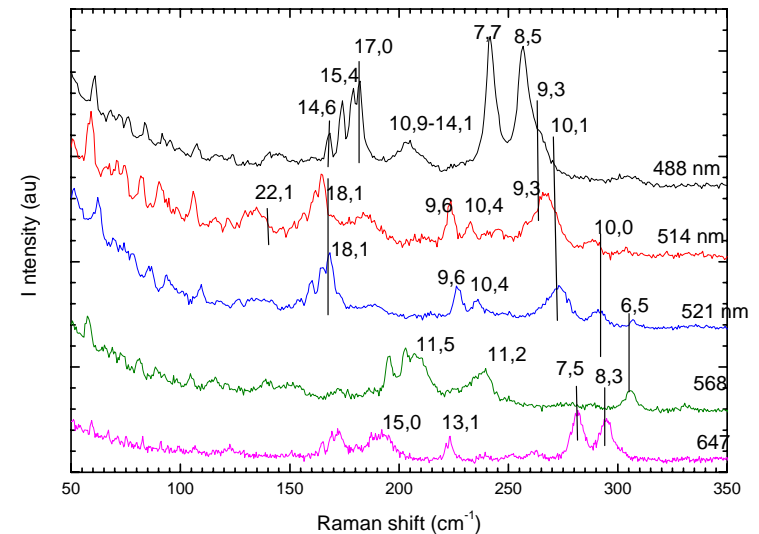
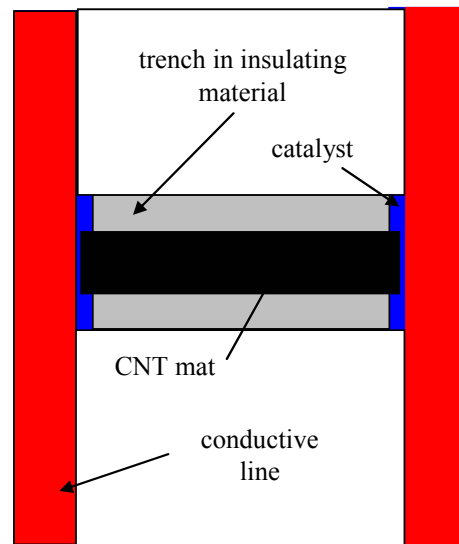
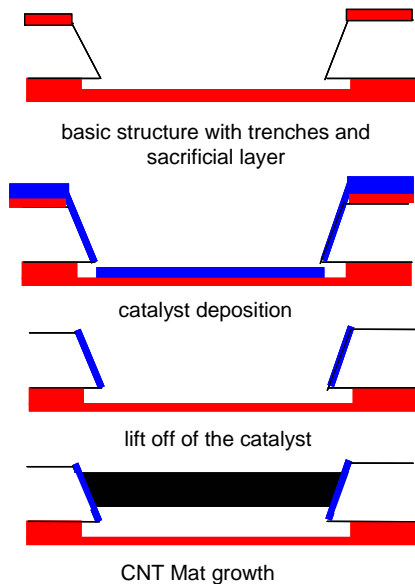
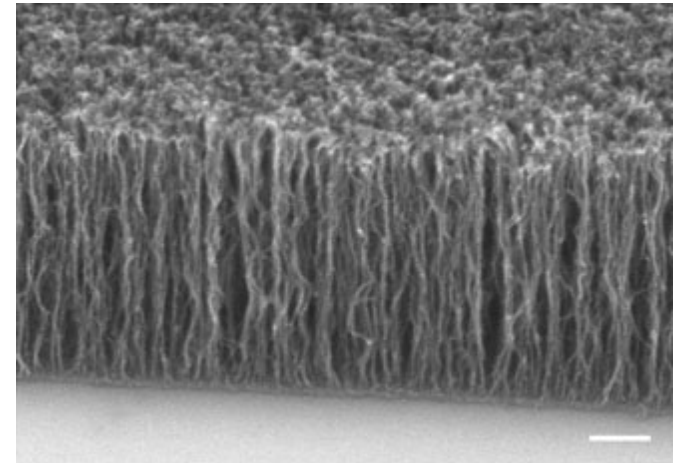
Previous work, Vias

- Leading work in Europe in 2003 was by Infineon
- Leading work presently Fujitsu
- They have reached $n=10^{11}$ cm^{-2}
- In addition, many technical problems



Technology

- High density nucleation for Vias – catalyst design
- Catalyst deposition (cluster dep)
- Characterisation (TEM, Raman)
- Top contacts
- Side-wall catalysts for Wires
- Coated trenches



NEMs

- Nanotubes have very high stiffness, low density, and large current carrying capacity
- In principle, good NEMs material

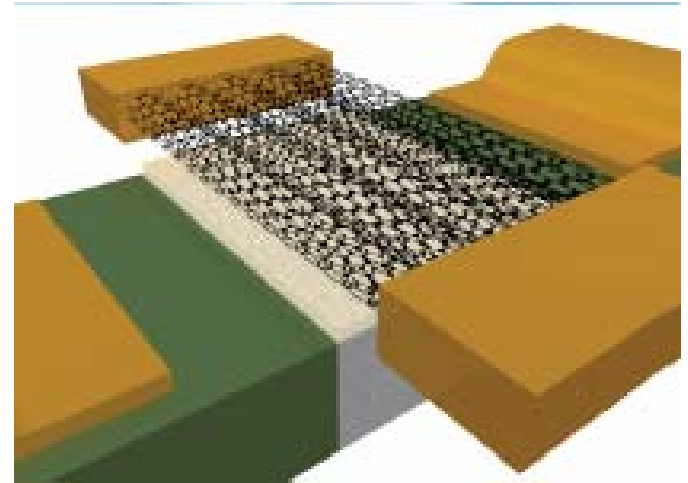
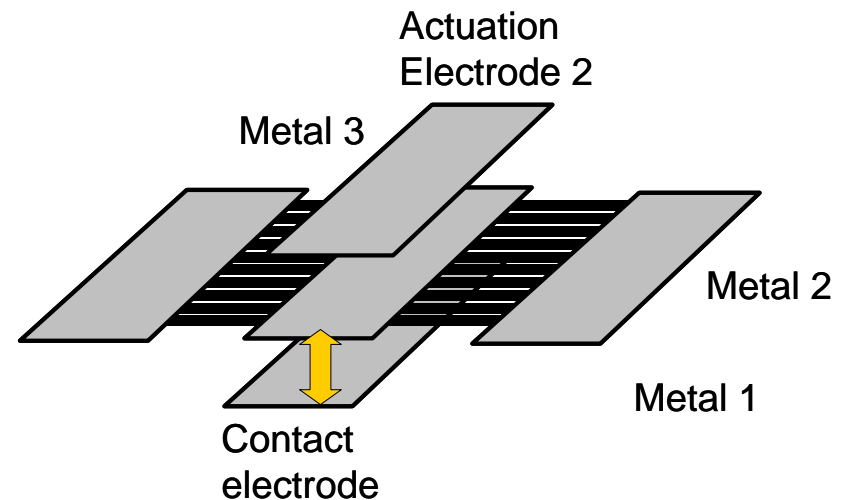


Fig. 3. Schematic of a NEMS relay.

- Horizontal RF NEMs switch
- Based of growth techniques developed for Wires



Expertise of partners

- Ucam - nanotube growth, catalyst design, characterisation
- CEA - nanotubes, processing, integration
- EPFL - NEMs, modelling, nanotubes
- Intel - processing, integration, end-user

Work packages

| WP | title |
|----|------------------------------------|
| 1 | Growth optimisation |
| 2 | Vertical interconnect technology |
| 3 | Horizontal interconnect technology |
| 4 | RF NEMs |

